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	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
	09/844,991	04/27/2001	Maurice Rivoire	AMAT/5297/DD/LOW K/JW	1361	
	32588	7590 06/18/2003				
	APPLIED MATERIALS, INC. 2881 SCOTT BLVD. M/S 2061 SANTA CLARA, CA 95050					
				EXAMINER		
				ROSE RO	ROSE, ROBERT A	
				11002, 110		
				ART UNIT	PAPER NUMBER	
				3723	\overline{C}	
				DATE MAILED: 06/18/2003	9	
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Please find below and/or attached an Office communication concerning this application or proceeding.

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Office Action Summary

Application No. 09/844,991

Applicant(s)

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Robert Rose

Art Unit **3723**

Rivoire et al

The MAILING DATE of this communication appears on the cover sheet with the correspondence address						
	for Reply IORTENED STATUTORY PERIOD FOR REPLY IS SET	TO EVPIDE throo MONTH(S) EROM				
THE	MAILING DATE OF THIS COMMUNICATION.					
	sions of time may be available under the provisions of 37 CFR 1.136 (a). In ag date of this communication.	no event, however, may a reply be timely filed after SIX (6) MONTHS from the				
- If the p	period for reply specified above is less than thirty (30) days, a reply within th period for reply is specified above, the maximum statutory period will apply a					
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any						
earned	d patent term adjustment. See 37 CFR 1.704(b).	nis construction, even it tailory these, may reacce any				
Status 1) 💢	Responsive to communication(s) filed on <i>Mar 31</i> , 2	onno				
2a) 🗌	This action is FINAL . 2b) ∇ This action					
_						
3) ∐ Dia=a-i	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11; 453 O.G. 213.					
	ition of Claims					
		is/are pending in the application.				
4	la) Of the above, claim(s)	is/are withdrawn from consideration.				
5) 🗆	Claim(s)	is/are allowed.				
6) 💢	Claim(s) <u>8-36</u>	is/are rejected.				
	Claim(s)	•				
		are subject to restriction and/or election requirement.				
Applica _	ation Papers					
_	the opening the objection to by the Examiner					
10)	The drawing(s) filed on is/are	a) \square accepted or b) \square objected to by the Examiner.				
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
11)		is: a) \square approved b) \square disapproved by the Examiner.				
	If approved, corrected drawings are required in reply t					
12) □	the comment of the examination of the examination	ner.				
	Acknowledgement is made of a claim for foreign or					
	Acknowledgement is made of a claim for foreign pr \Box All b) \Box Some* c) \Box None of:	flority under 35 U.S.C. § 119(a)-(a) or (f).				
		ocuments have been received in this National Stage				
	application from the International Burea See the attached detailed Office action for a list of the	au (PCT Rule 17.2(a)).				
	Acknowledgement is made of a claim for domestic					
a) [-					
15)	Acknowledgement is made of a claim for domestic					
Attachme		_				
_	otice of References Cited (PTO-892)	4) Interview Summary (PTO-413) Paper No(s).				
	otice of Draftsperson's Patent Drawing Review (PTO-948) formation Disclosure Statement(s) (PTO-1449) Paper No(s).	5) Notice of Informal Patent Application (PTO-152)				
o, M	officiation disclosure oratement(s) (FTO-1745) raper No(s).	6) Other:				

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DETAILED ACTION

- 1. Receipt is acknowledged of Applicant's Prior Art Statement, filed March 31, 2003.
- 2. Applicant's election without traverse of Group II(Claims 8-29), drawn to a method of planarizing a surface in Paper No. 7 is acknowledged.
- 3. Claims 1-7 have been canceled.
- 4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claims 8, 10-13, 15-19, 21-24, 26-29, are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Homma et al. Homma et al disclose a method for polishing organosilicate layer on a substrate comprising all of the subject matter set forth in applicant's claims above. Note the use of an aqueous solution of abrasive within the pH range recited. The values of pressure and platen rotational speed disclosed in Homma et al are within the recited ranges of polishing pressure and platen rotational speed.
- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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7. Claims 9, 14, 20, 25, and 30-36 are rejected under 35 U.S.C. 103(a) as being unpatentable

over Homma et al. It is known from the prior art process disclosed in Homma et al to use silicon

dioxide colloidal or fumed slurry to polish insulating layers on wafers(column 1, lines 13-34).

To substitute an inexpensive abrasive such as silicon dioxide for the ceria abrasive in the method

of Homma et al would have been at most an obvious matter of design choice in the absence of a

showing of criticality by way of unexpected results achieved through the use of the specific

abrasive chosen. Likewise, in the absence of a showing of unexpected results, the percent weight

of the abrasive slurry would constitute an obvious matter of design choice which would be

readily arrived at by routine experimentation by those of ordinary skill in the wafer polishing art.

8. Any inquiry concerning this communication should be directed to Robert Rose at

telephone number (703) 308-1360.

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June 13, 2003.

ROBERT A. ROSE PRIMARY EXAMINER ART UNIT 323 Page 3